

MONSHOUWER et al. -- 09/940,818  
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IN THE ABSTRACT:

Please delete the present Abstract and replace it with the following new Abstract:

In a method of measuring, in a lithographic manufacturing process using a lithographic projection apparatus, overlay between a resist layer ( $RL$ ), in which a mask pattern ( $G$ ) is to be imaged, and a substrate ( $W$ ), use is made of an alignment-measuring device ( $AS_1, AS_2$ ) forming part of the apparatus and of specific overlay marks ( $P_{10}, P_{11}$ ) in the substrate and resist layer. These marks have periodic structures with periods ( $PE_{10}, PE_{11}$ ) which cannot be resolved by the alignment device, but generate an interference pattern ( $Pb$ ) having a period ( $PE_0$ ) corresponding to the period of a reference mark ( $M_1, M_2$ ) of the alignment device.

Fig. 5